

HOGAN & HARTSON L.L.P.

500 SOUTH GRAND AVENUE
SUITE 1900
LOS ANGELES, CA 90071

Tel.: (213) 337-6700
Fax: (213) 337-6701

RECEIVED
CENTRAL FAX CENTER

JUN 07 2006

BALTIMORE
BEIJING
BERLIN
BOULDER
BRUSSELS
BUDAPEST
CARACAS
COLORADO SPRINGS
DENVER
GENEVA
HONG KONG
LONDON
LOS ANGELES
MIAMI
MOSCOW
MUNICH
NEW YORK
NORTHERN VIRGINIA
PARIS
SHANGHAI
TOKYO
WARSZAWA
WASHINGTON, D.C.

IMPORTANT NOTICE**TELECOPY/FACSIMILE COVER LETTER**

TO: Office of Initial Patent Examination's
Filing Receipt Corrections

DATE: 6/7/2006

FROM: Mr. Lenin V. Zeledón
Intellectual Property Specialist

TIME: 10:26 AM

TOTAL NO. OF PAGES, INCLUDING COVER: 5

The attached information is **CONFIDENTIAL** and is intended only for the use of the addressee(s) named above. If the reader of this message is not the intended recipient(s) or the employee or agent responsible for delivering the message to the intended recipient(s), please note that any dissemination, distribution or copying of this communication is strictly prohibited. Anyone who receives this communication in error should notify us immediately by telephone and return the original message to us at the above address via the U.S. Mail.

MESSAGE:**U.S. Patent Application 10/553,272; Our Ref. No.: 89227.0010**

Please note the omission on the attached Filing Receipt. The "Applicant's" section, the following names were left out; Toshio YAMANAKA, Yuki TAKIGUCHI, Kaoru NISHIKAWA as it appears on the priority claimed application PCT/JP2004/005273.

Please provide us with the Corrected Filing Receipt as soon as possible.

Thank you.

Enclosure: (Official Filing Receipt, Copy of International WO/2004/092838 page)

FOR INTERNAL PURPOSES ONLY

TELECOPY/FAX NUMBER: 1-571-273-8300

CLIENT NUMBER: 89227.0010

ATTORNEY BILLING NUMBER: Lenin V. Zeledón

CONFIRMATION NUMBER: 213-337-6701

RECEIVED
CENTRAL FAX CENTER

UNITED STATES PATENT AND TRADEMARK OFFICE

JUN 07 2006

MANERA Corp. / DAN

UNITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trademark Office
Address: COMMISSIONER FOR PATENTS
P.O. Box 1450
Alexandria, Virginia 22313-1450
www.uspto.gov

APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY.DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/553,272	10/12/2005	1712	3350	89227.0010	1	49	1

CONFIRMATION NO. 6639

000026021
 HOGAN & HARTSON L.L.P.
 500 S. GRAND AVENUE
 SUITE 1900
 LOS ANGELES, CA 90071-2611

FILING RECEIPT



OC000000019005403

Date Mailed: 05/31/2006

Receipt is acknowledged of this regular Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please mail to the Commissioner for Patents P.O. Box 1450 Alexandria Va 22313-1450. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

Applicant(s)

Koji Okada, Osaka, JAPAN;
 Toshio Yamanaka, Osaka, JAPAN;

Power of Attorney: The patent practitioners associated with Customer Number **000026021**.

Domestic Priority data as claimed by applicant

This application is a 371 of PCT/JP04/05273 04/13/2004

Foreign Applications

JAPAN 2003-110359 04/15/2003
 JAPAN 2003-117947 04/23/2003
 JAPAN 2003-124026 04/28/2003
 JAPAN 2003-123192 04/28/2003

If Required, Foreign Filing License Granted: 05/30/2006

The country code and number of your priority application, to be used for filing abroad under the Paris Convention, is **US10/553,272**

Projected Publication Date: 09/07/2006

Non-Publication Request: No

Early Publication Request: No

RECEIVED

✓ JUN 06 2006
 DOCKETING

Title

Photosensitive resin composition capable of being developed with aqueous developer and photosensitive dry film resist, and use thereof

Preliminary Class

525

PROTECTING YOUR INVENTION OUTSIDE THE UNITED STATES

Since the rights granted by a U.S. patent extend only throughout the territory of the United States and have no effect in a foreign country, an inventor who wishes patent protection in another country must apply for a patent in a specific country or in regional patent offices. Applicants may wish to consider the filing of an international application under the Patent Cooperation Treaty (PCT). An international (PCT) application generally has the same effect as a regular national patent application in each PCT-member country. The PCT process simplifies the filing of patent applications on the same invention in member countries, but does not result in a grant of "an international patent" and does not eliminate the need of applicants to file additional documents and fees in countries where patent protection is desired.

Almost every country has its own patent law, and a person desiring a patent in a particular country must make an application for patent in that country in accordance with its particular laws. Since the laws of many countries differ in various respects from the patent law of the United States, applicants are advised to seek guidance from specific foreign countries to ensure that patent rights are not lost prematurely.

Applicants also are advised that in the case of inventions made in the United States, the Director of the USPTO must issue a license before applicants can apply for a patent in a foreign country. The filing of a U.S. patent application serves as a request for a foreign filing license. The application's filing receipt contains further information and guidance as to the status of applicant's license for foreign filing.

Applicants may wish to consult the USPTO booklet, "General Information Concerning Patents" (specifically, the section entitled "Treaties and Foreign Patents") for more information on timeframes and deadlines for filing foreign patent applications. The guide is available either by contacting the USPTO Contact Center at 800-786-9199, or it can be viewed on the USPTO website at <http://www.uspto.gov/web/offices/pac/doc/general/index.html>.

For information on preventing theft of your intellectual property (patents, trademarks and copyrights), you may wish to consult the U.S. Government website, <http://www.stopfakes.gov>. Part of a Department of Commerce initiative, this website includes self-help "toolkits" giving innovators guidance on how to protect intellectual property in specific countries such as China, Korea and Mexico. For questions regarding patent enforcement issues, applicants may call the U.S. Government hotline at 1-866-999-HALT (1-866-999-4158).

LICENSE FOR FOREIGN FILING UNDER**Title 35, United States Code, Section 184****Title 37, Code of Federal Regulations, 5.11 & 5.15****GRANTED**

The applicant has been granted a license under 35 U.S.C. 184, if the phrase "IF REQUIRED, FOREIGN FILING LICENSE GRANTED" followed by a date appears on this form. Such licenses are issued in all applications where the conditions for issuance of a license have been met, regardless of whether or not a license may be required as set forth in 37 CFR 5.15. The scope and limitations of this license are set forth in 37 CFR 5.15(a) unless an earlier license has been issued under 37 CFR 5.15(b). The license is subject to revocation upon written notification. The date indicated is the effective date of the license, unless an earlier license of similar scope has been granted

under 37 CFR 5.13 or 5.14.

This license is to be retained by the licensee and may be used at any time on or after the effective date thereof unless it is revoked. This license is automatically transferred to any related applications(s) filed under 37 CFR 1.53(d). This license is not retroactive.

The grant of a license does not in any way lessen the responsibility of a licensee for the security of the subject matter as imposed by any Government contract or the provisions of existing laws relating to espionage and the national security or the export of technical data. Licensees should apprise themselves of current regulations especially with respect to certain countries, of other agencies, particularly the Office of Defense Trade Controls, Department of State (with respect to Arms, Munitions and Implements of War (22 CFR 121-128)); the Bureau of Industry and Security, Department of Commerce (15 CFR parts 730-774); the Office of Foreign Assets Control, Department of Treasury (31 CFR Parts 500+) and the Department of Energy.

NOT GRANTED

No license under 35 U.S.C. 184 has been granted at this time, if the phrase "IF REQUIRED, FOREIGN FILING LICENSE GRANTED" DOES NOT appear on this form. Applicant may still petition for a license under 37 CFR 5.12, if a license is desired before the expiration of 6 months from the filing date of the application. If 6 months has lapsed from the filing date of this application and the licensee has not received any indication of a secrecy order under 35 U.S.C. 181, the licensee may foreign file the application pursuant to 37 CFR 5.15(b).



WIPO PatentScope
Activities & Services

Search Contact Home
Español · Français

Home > Activities & Services > PatentScope > Patent Search



Search res...

Home
About Patents
Patent Search
Content
Terms & Conditions
Glossary
Other Collections
PCT Resources
PCT Electronic Filing
Patent & Technical Information
Statistics
Law of Patents
Meetings
E-mail Updates
Contact

Related Links
International Patent Classification
Natural Language IPC Search
Standards & Documentation

[Printable version]

(WO/2004/092838) PHOTORESISTIVE RESIN COMPOSITION CAPABLE OF BEING DEVELOPED WITH AQUEOUS DEVELOPER AND PHOTORESISTIVE DRY FILM AND USE THEREOF

Biblio. Data Description Claims National Phase Notices Documents

Latest bibliographic data on file with the International Bureau

Publication Number: WO/2004/092838 International Application No.: PCT/JP2004/005273
Publication Date: 28.10.2004 International Filing Date: 13.04.2004

Int. Class.: G03F 7/037 (2006.01), H05K 3/28 (2006.01)

Applicants: KANEKA CORPORATION [JP/JP]; 2-4, Nakanoshima 3-chome, Kita-ku, Osaka-shi, Osaka 530-0004
(JP) (All Except US).
OKADA, Koji (US Only).
YAMANAKA, Toshio (US Only).
TAKIGUCHI, Yuki (US Only).
NISHIKAWA, Kaoru (US Only).

Inventors: OKADA, Koji.
YAMANAKA, Toshio.
TAKIGUCHI, Yuki.
NISHIKAWA, Kaoru.

Agent: HARA, Kenzo; HARAKENZO WORLD PATENT & TRADEMARK PATENT LAW FIRM, Daiwa Minamimorimachi Building, 2-6, Tenjinbashi 2-chome, Kita, Kita-ku, Osaka-shi, Osaka 530004

Priority Data: 2003-110359 15.04.2003 JP
2003-117947 23.04.2003 JP
2003-124026 28.04.2003 JP
2003-123192 28.04.2003 JP

Title: PHOTORESISTIVE RESIN COMPOSITION CAPABLE OF BEING DEVELOPED WITH AQUEOUS DEVELOPER AND PHOTORESISTIVE DRY FILM RESIST, AND USE THEREOF

Abstract: A photoreactive resin composition, which comprises (A) a base resin component being at least 1) a polyimide resin containing at least one of a hydroxyl group and a carboxyl group in the structure thereof, (A-2) a polyamide resin containing at least one of a hydroxyl group and a carboxyl group in the structure thereof, and (A-3) a photoreactive imide (meth) acrylsiloxane oligomer, and (B) a (meth) acrylsiloxane oligomer. The photoreactive resin composition allows the achievement of the following characteristics: (1) the realization and improvement of aqueous development, (2) the improvement of the utility of the irradiated film, (3) the improvement of physical properties after curing, and (4) the simplification of the structure of a printed wiring board, and accordingly can be suitably used, in particular, for a photoreactive dry film resist and a laminate, a printed wiring board and the like using the film resist.

Designated States: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KP, KR, KZ, LC, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW, African Regional Intellectual Property Org. (ARIPO) (BW, GH, GM, KE, LS, MW, MZ, SD, SL, ZM, ZW)
Eurasian Patent Organization (EAPO) (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM)
European Patent Office (EPO) (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, MC, NL, PL, PT, RO, SE, SI, SK, TR)
African Intellectual Property Organization (OAPI) (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, I, NG & LANG... 6/7/2006
NE, SN, TD, TO)